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(12) **United States Design Patent**  
**Gunther et al.**

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(54) **TARGET PROFILE FOR A PHYSICAL VAPOR DEPOSITION CHAMBER TARGET**

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(\*\*) Term: **15 Years**

(57) **CLAIM**

We claim the ornamental design for a target profile for a physical vapor deposition chamber target, as shown and described.

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(51) **LOC (14) Cl.** ..... **13-03**

(52) **U.S. Cl.**  
USPC ..... **D13/182**

(58) **Field of Classification Search**  
USPC ..... D23/249, 259, 262, 269; D15/138, 139, D15/143, 144, 144.1, 144.2, 150, 199; D13/118, 122, 133, 162, 182, 184, 199; D22/113, 119  
CPC ..... H01J 37/3414; H01J 37/3423; H01L 21/02631; H01L 2221/68363; H01L 2224/75186-75189; H01L 21/67742; H01L 21/0226; H01L 21/02263; H01L (Continued)

**DESCRIPTION**

FIG. 1 is a top perspective view of a sputtering target for a physical vapor deposition chamber, according to one embodiment of the novel design.

FIG. 2 is a top plan view thereof.

FIG. 3 is a bottom plan view thereof.

FIG. 4 is a right side elevation view thereof.

FIG. 5 is a left side elevation view thereof.

FIG. 6 is a front elevation thereof.

FIG. 7 is a back elevation view thereof; and,

FIG. 8 is an enlarged partial right side elevation view showing portions of the design in greater detail.

The dash-dash broken lines in FIGS. 1-8 represent unclaimed environment and form no part of the claimed design.

The short dash-dot lines on FIG. 4 and FIG. 8 depict the bounds of the region taken from FIG. 4 to be enlarged on FIG. 8 and form no part of the claimed design.

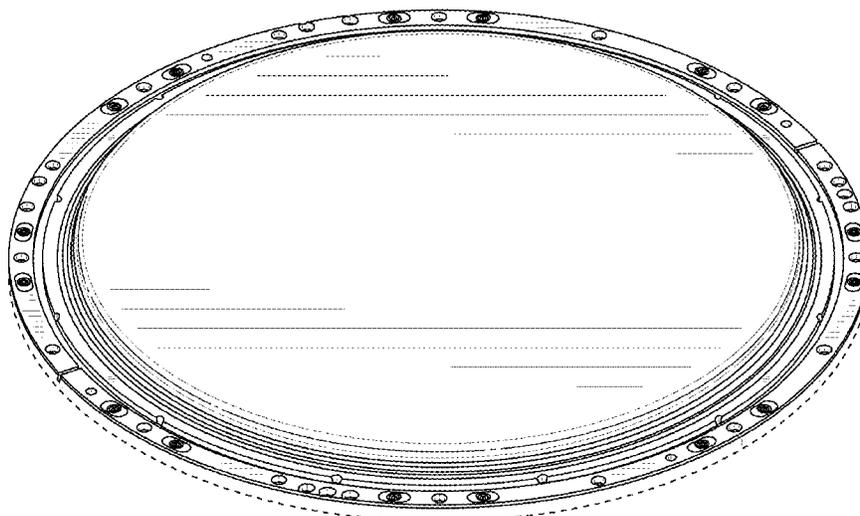
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**1 Claim, 6 Drawing Sheets**



(58) **Field of Classification Search**  
 CPC .. 21/02266; H01L 21/02269; H01L 21/02271;  
 F16J 7/00; E04D 13/14; C23C 14/3407;  
 C23C 14/35  
 See application file for complete search history.

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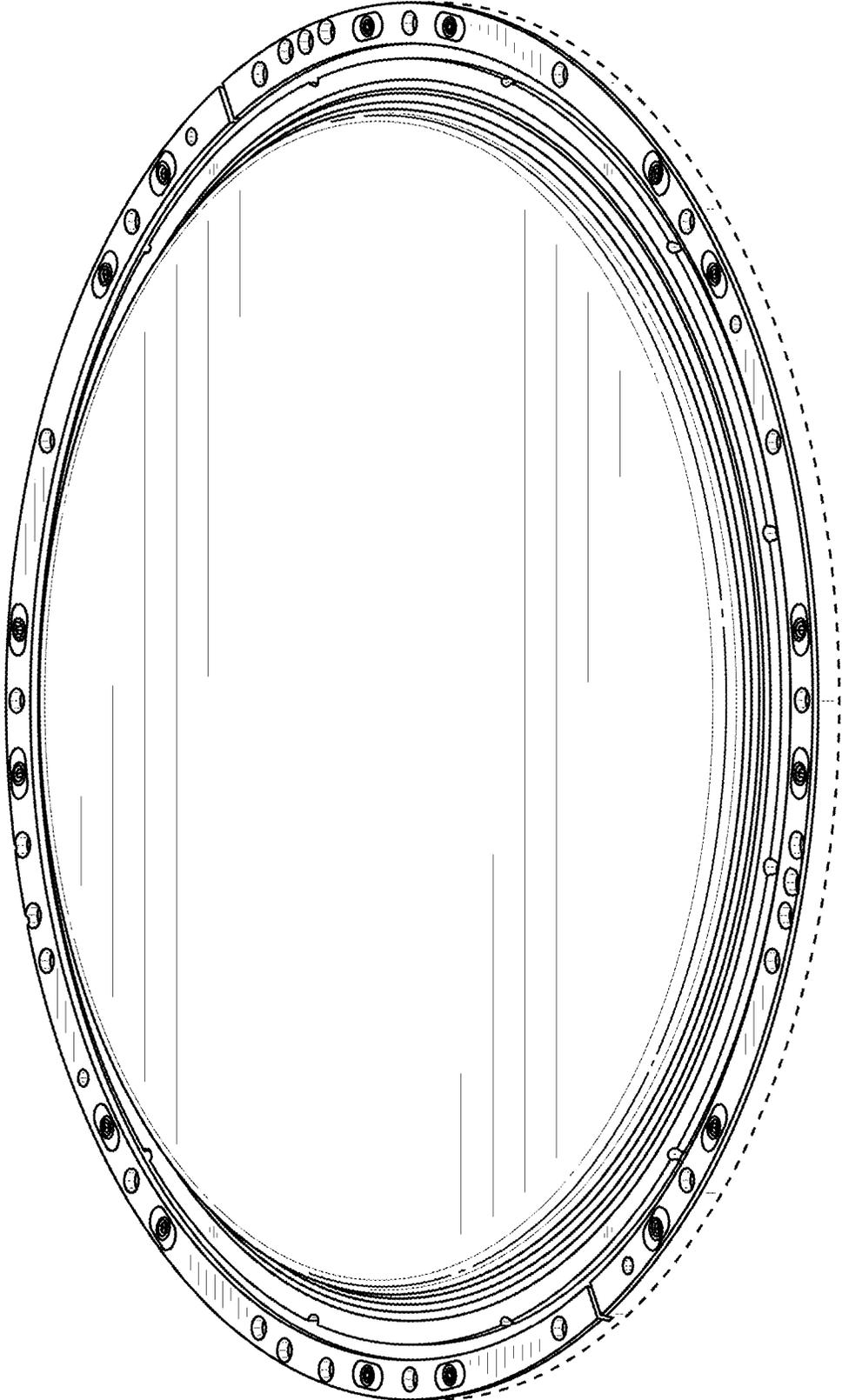
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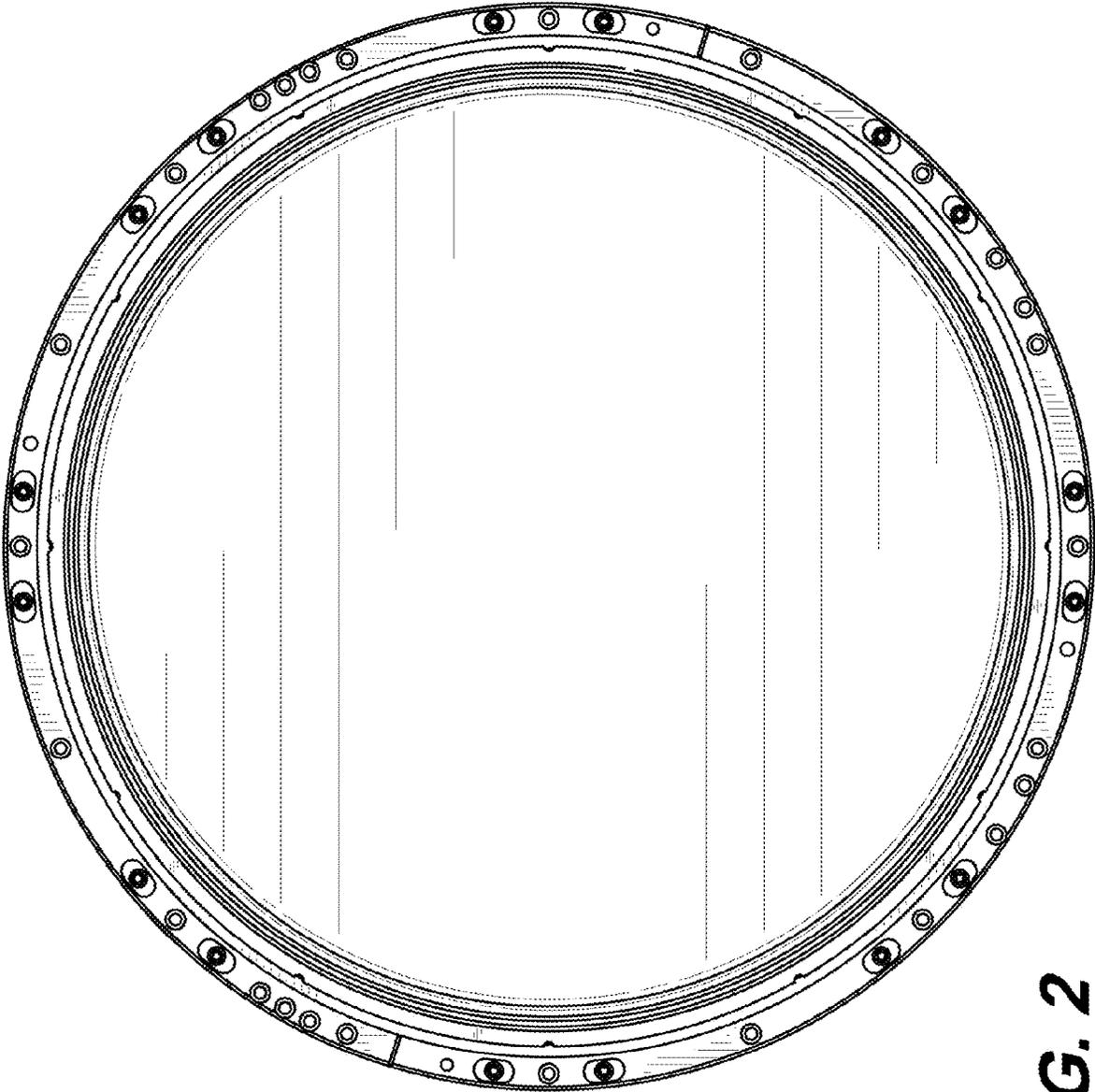
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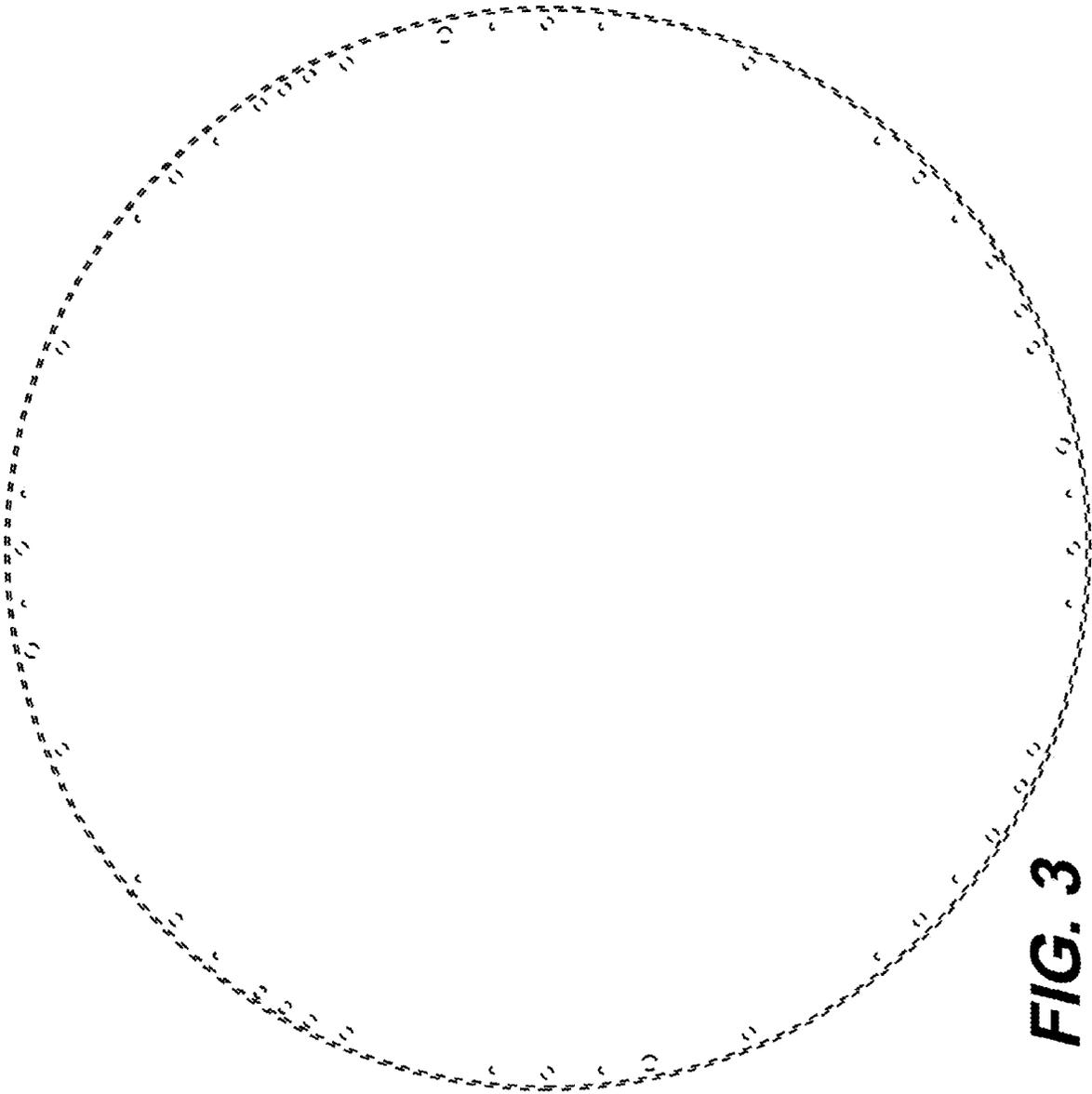
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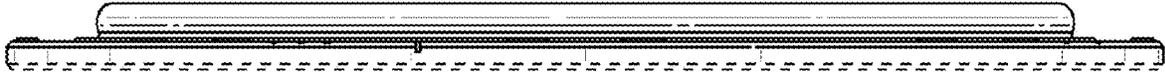
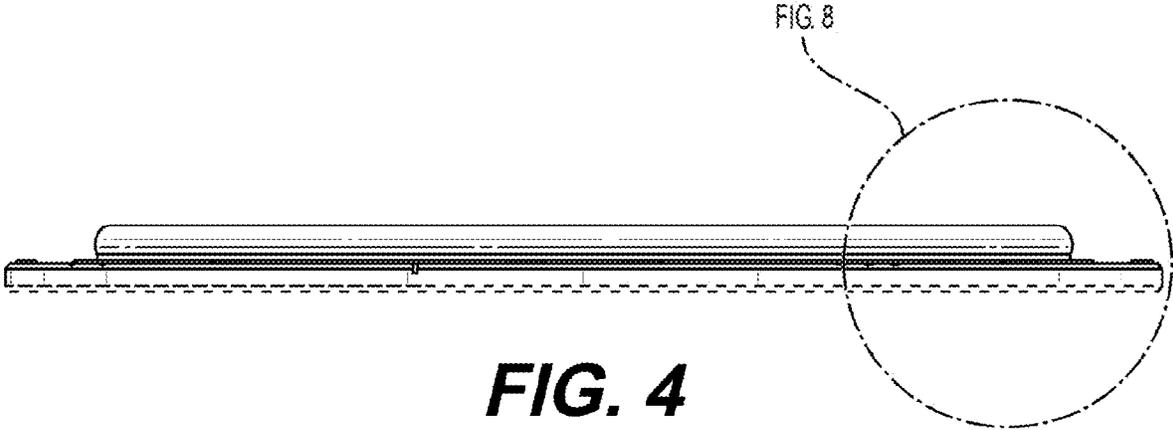
**FIG. 1**



**FIG. 2**

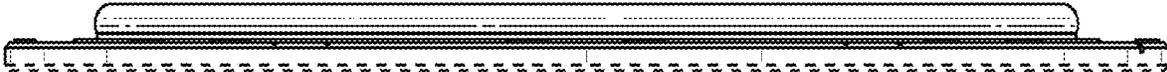


**FIG. 3**

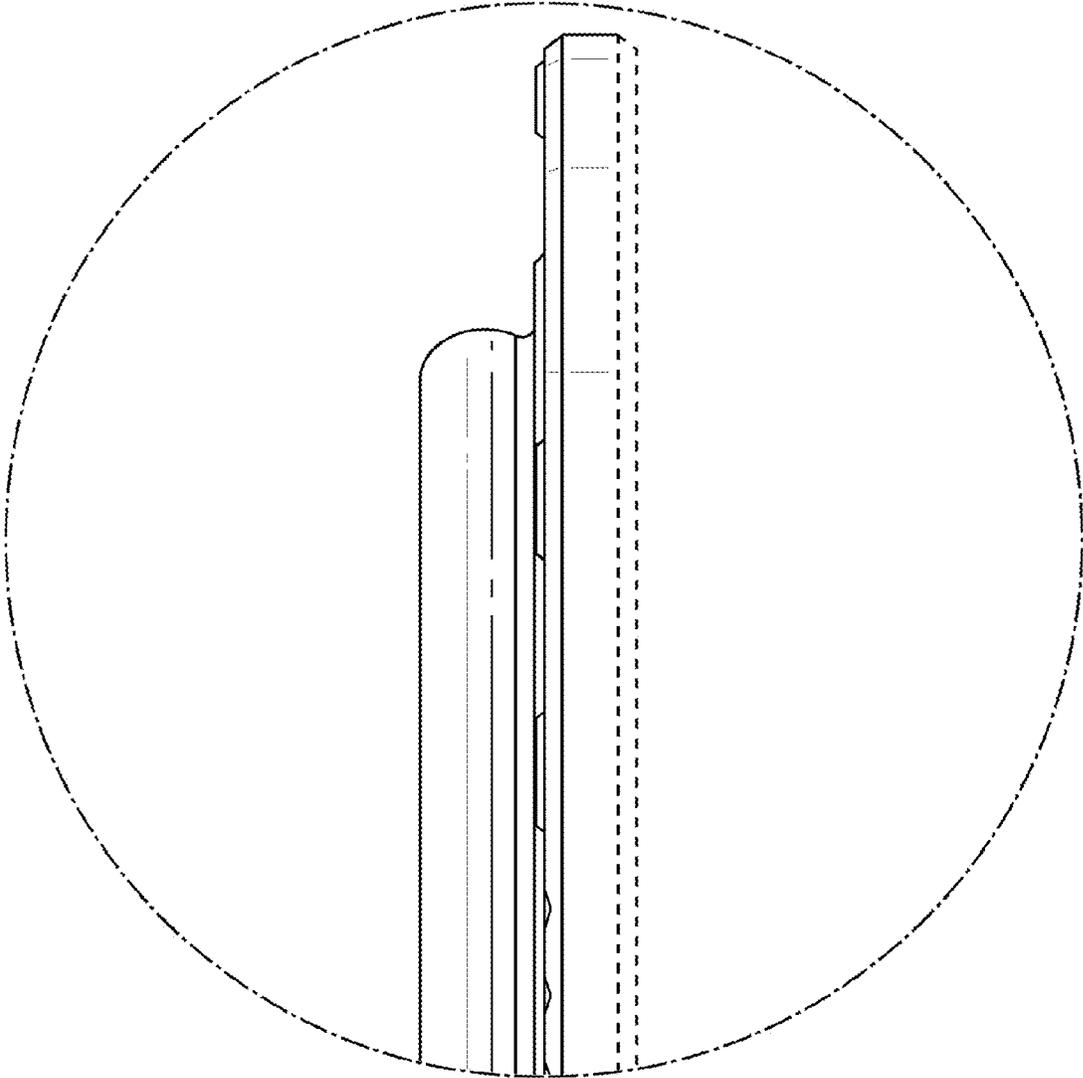




**FIG. 6**



**FIG. 7**



**FIG. 8**